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	Class	Subclass

PATENT NUMBER

**U.S. UTILITY Patent Application**

O.I.P.E.	PATENT DATE
 SCANNED <u>TR2</u> <u>04/05/03</u>	

APPLICATION NO.	CONT/PRIOR	CLASS	SUBCLASS	ART UNIT	EXAMINER
09/991166	D F	438	713	2812	Reed - Kandy

## APPlicants

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Method of reducing particulates in a plasma etch chamber during a metal etch process

**ISSUING CLASSIFICATION**

TERMINAL DISCLAIMER	DRAWINGS			CLAIMS ALLOWED	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G.
<input type="checkbox"/> The term of this patent subsequent to _____ (date) has been disclaimed.				NOTICE OF ALLOWANCE MAILED	
	_____ (Assistant Examiner) _____ (Date)				
<input type="checkbox"/> The term of this patent shall not extend beyond the expiration date of U.S Patent. No. _____  _____  _____				ISSUE FEE	
	_____ (Primary Examiner) _____ (Date)			Amount Due	Date Paid
<input type="checkbox"/> The terminal _____ months of this patent have been disclaimed.				ISSUE BATCH NUMBER	
	_____ (Legal Instruments Examiner) _____ (Date)				

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